

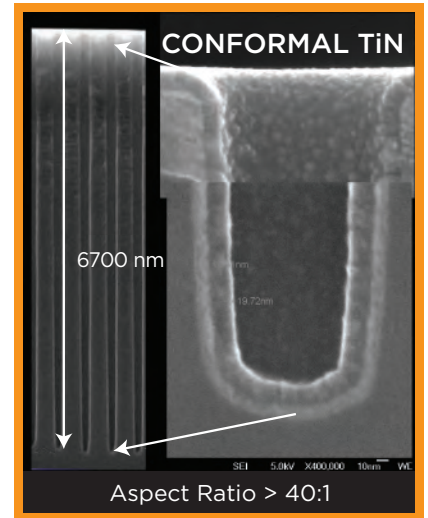
NANOLAYER DEPOSITION

Nanolayer deposition (NLD) is a patented approach for depositing thin conformal films that combines many of the favorable aspects of atomic layer deposition with the higher deposition rates associated with pulsed layer deposition. Tegal began developing NLD™ in the mid-1990s and has since been awarded six US patents pertaining to NLD™ processing for its efforts.

This patent portfolio provides a unique, exploitable, and defensible intellectual property position in thin film deposition

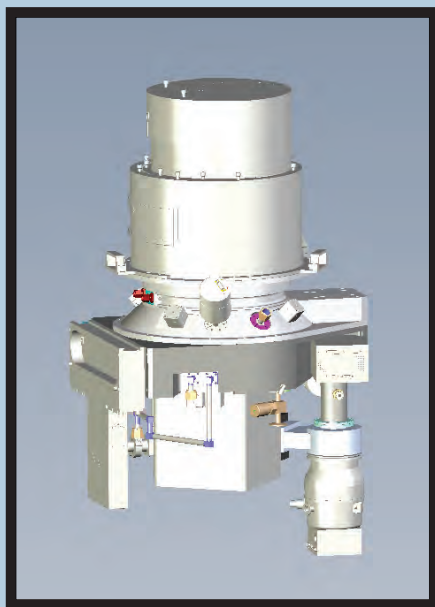
technology combining unique aspects of pulsed chemical vapor deposition (PCVD) and atomic layer deposition (ALD) technologies.

NLD™ is used to deposit metals and dielectric films at higher rates with considerably higher conformality than conventional CVD. Many metallorganic precursors are available today that are compatible with NLD™ technology and most existing ALD hardware sets that are capable of delivering MOCVD precursors are compatible with NLD™.



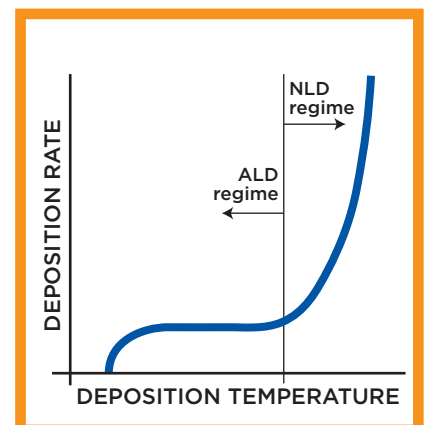
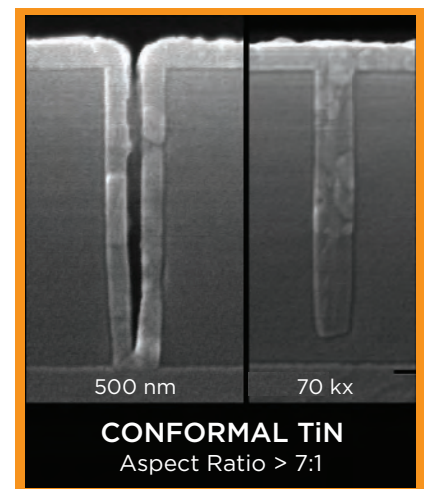
NANOLAYER DEPOSITION TECHNOLOGY HIGHLIGHTS

- Higher deposition rates than ALD
- Improved conformality over standard CVD and PECVD
- Wide range of compatible MOCVD precursors
- Compatible with dielectric and conductive films



Portfolio of NLD Process Patents

6,610,169
6,756,318
7,235,484
7,442,615
7,713,592
7,867,905
20100285237 (pending)



tegal

CONTACT: Robert Ditzio, Senior Director, R&D | Tegal Corporation
140 Second Street, Suite 318, Petaluma CA 94952 | 707 765 5617 | rditzio@tegal.com
Confidential and Proprietary Information contained herein not authorized for release to other parties